

# GaN-based Robust Micro Pressure and Temperature Sensors for Extreme Planetary Environments

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# Acknowledgements

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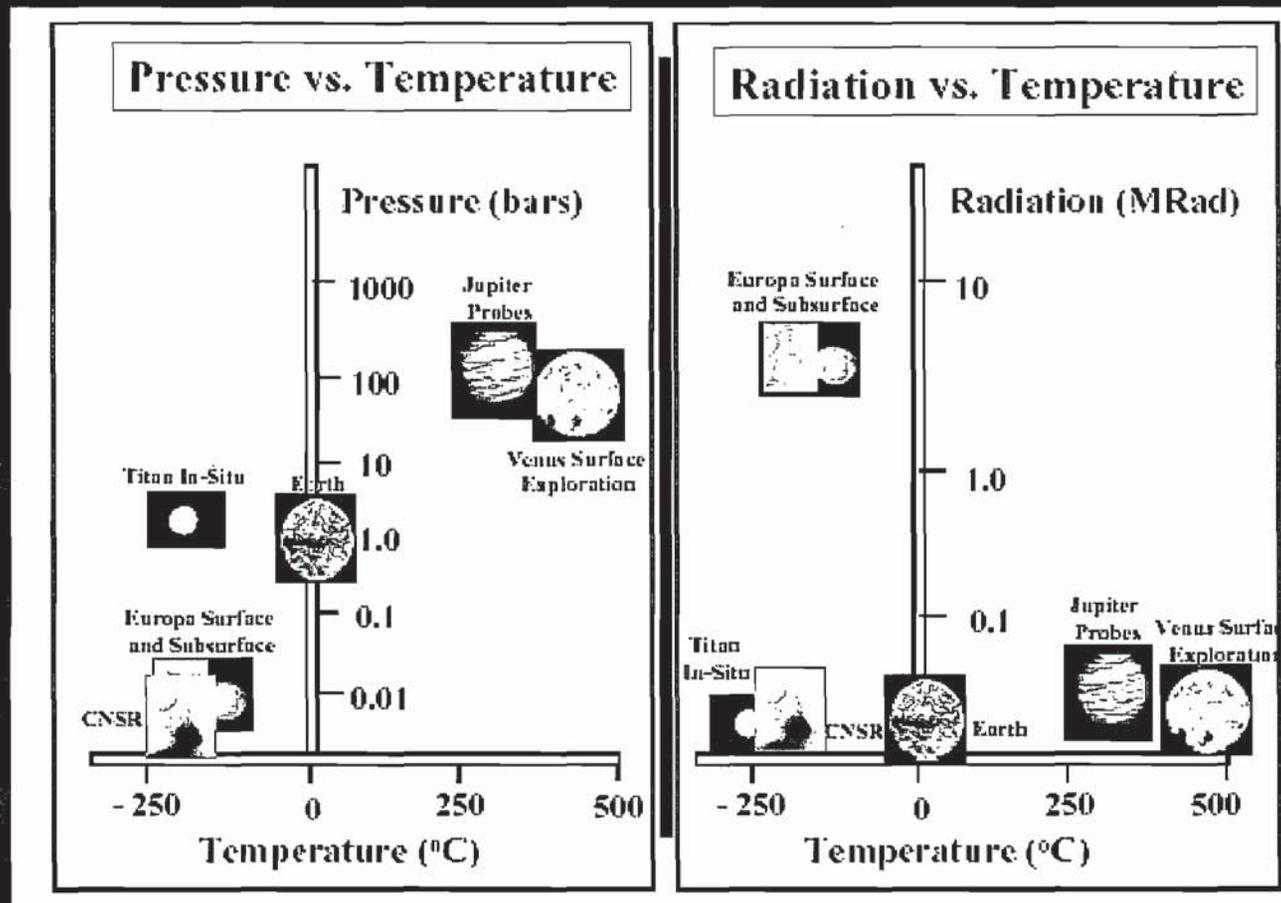
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ARC



# Temperature, Pressure, and Radiation in Reference Missions



Chris Moore, "Technology Development for Extreme Environments Systems"  
Workshop on Extreme Environments Technologies for Space Explorations, Pasadena,  
May 14, 2003. Kyung-ah Son (818)393-2335, kson@jpl.nasa.gov

# Extreme Environments in Five Space Science Reference Missions

All five missions have to survive in extreme environments.

Mission	Low Temp.	High Temp.	High Rad.	High P.
Venus Surface Exploration & sample return		460 C		90 bar
Giant Planets Deep Probes	-140 C	380 C		100 bar
Comets Nucleus Sample Return	-140 C			
Titan <i>In Situ</i>	-180 C			
Europa Surface & Subsurface	-160 C		5 MRad	

**Chris Moore**, "Technology Development for Extreme Environments Systems"  
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# AlGaN/GaN Hetero Structure-based Micro Sensors

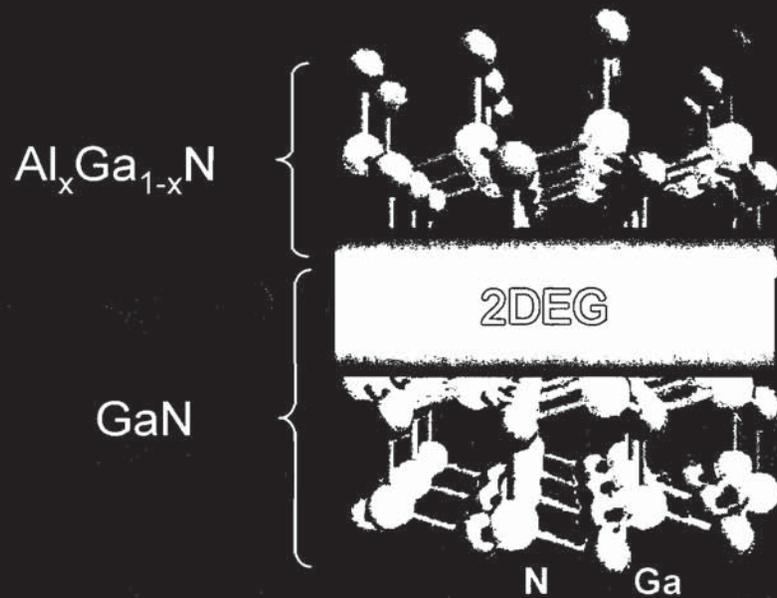
## Merits:

- Superior materials properties; Ideal for extreme environments

Mechanically strong, chemically & thermally inert, radiation hard  
Minimal in unwanted optical or thermal generation of charge carriers

- Small volume, low mass, and low power requirement
- Novel device concept and simple & reproducible fabrication
- Monolithic integration to GaN-based RF transceiver

# AlGa<sub>x</sub>N/GaN Heterostructure Devices for Pressure Sensing



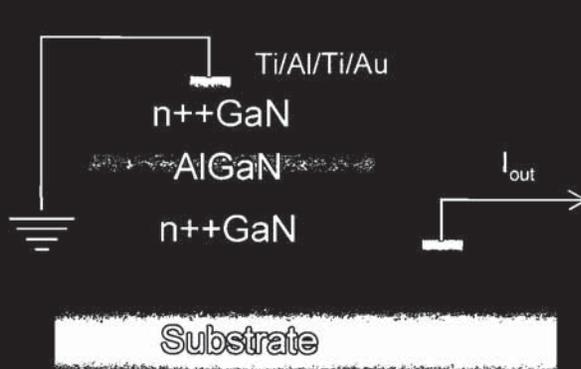
- ❖ Sheet charge layer (2-Dimensional Electron Gas) at the interface of GaN and AlGa<sub>x</sub>N

- ❖ Applied stress/pressure

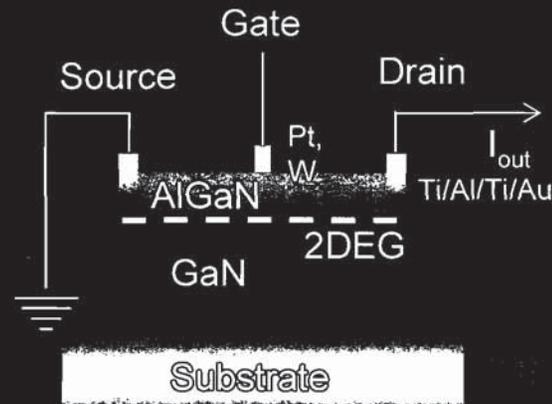


Modulation of the electron concentration & the conduction in the 2DEG.

# AlGaN/GaN based High Pressure Sensors



Schematic cross section of  
**n-GaN/AlGaN/n-GaN (n-I-n)**  
vertical transport diode  
sensor



Schematic cross section of  
**AlGaN/GaN HEMT** sensor

Expected operational range:

0-10 kbar with 1 mbar accuracy

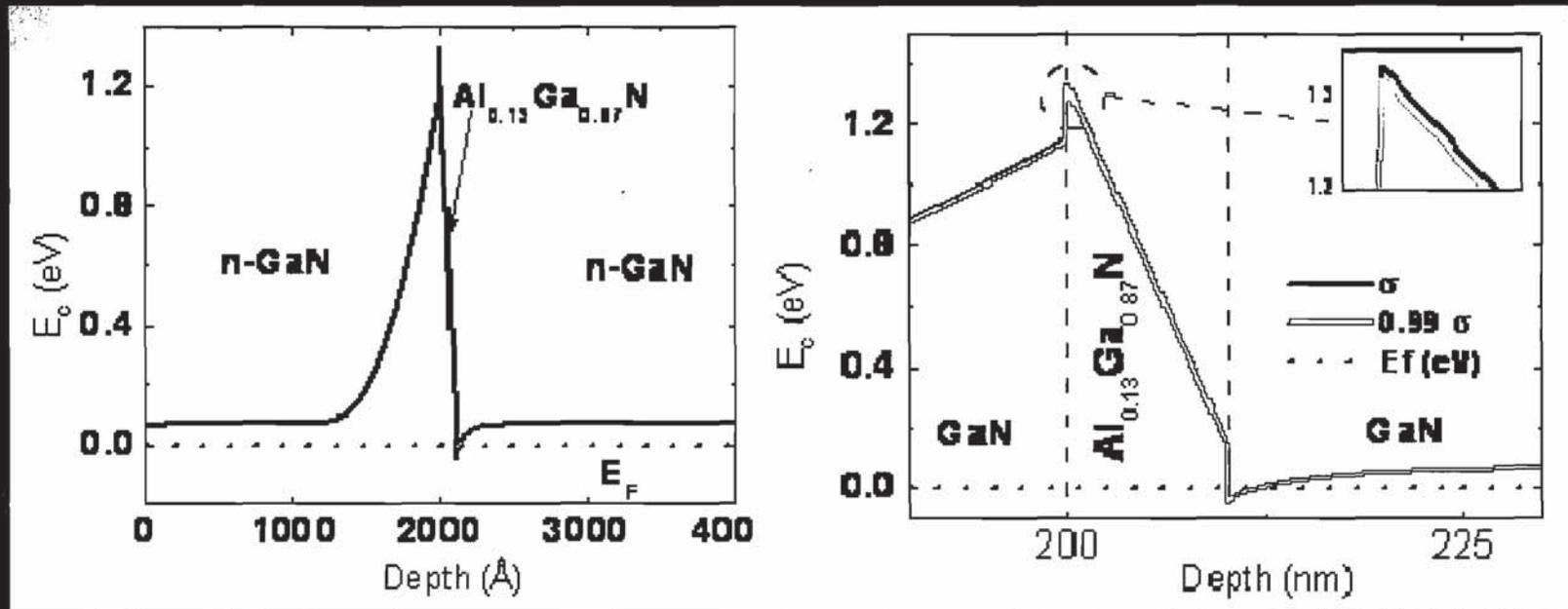
30 K - 870 K with 0.1 K accuracy

Expected volume:  $\sim 1 \text{ cm}^3$

mass:  $< 5 \text{ g}$

power requirement:  $< 10 \text{ mW}$

# Conduction Band Diagram of GaN/Al<sub>x</sub>Ga<sub>1-x</sub>N/GaN sensor

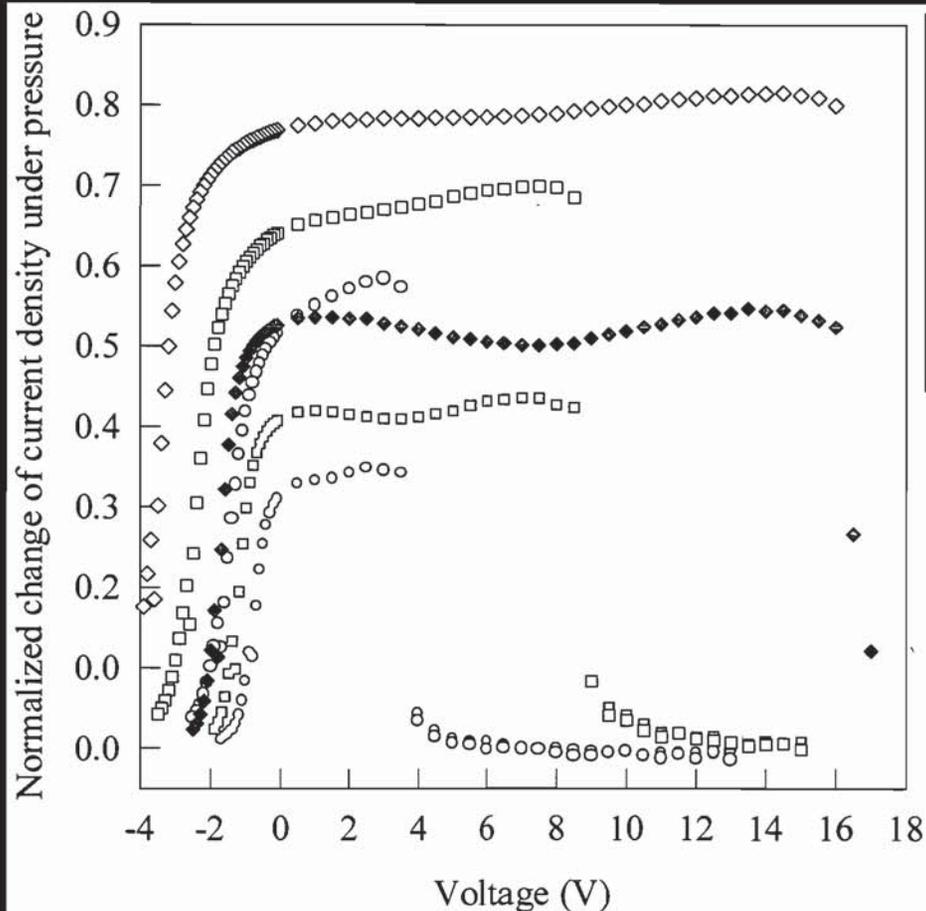


## Conduction band diagram of n-GaN/Al<sub>0.13</sub>Ga<sub>0.87</sub>N/n-GaN

- for 10 nm thick undoped Al<sub>0.13</sub>Ga<sub>0.87</sub>N and  $2 \times 10^{17} \text{ cm}^{-3}$  doping in both n-GaN regions
- estimated polarization charge at the Al<sub>0.13</sub>Ga<sub>0.87</sub>N/n-GaN:  $7.24 \times 10^{12} \text{ ecm}^{-2}$
- calculated barrier height: 1.33 eV
- **12 meV decrease of barrier height expected from 1% reduction of polarization charge; 60 % increase in thermionic emission current over the barrier.**

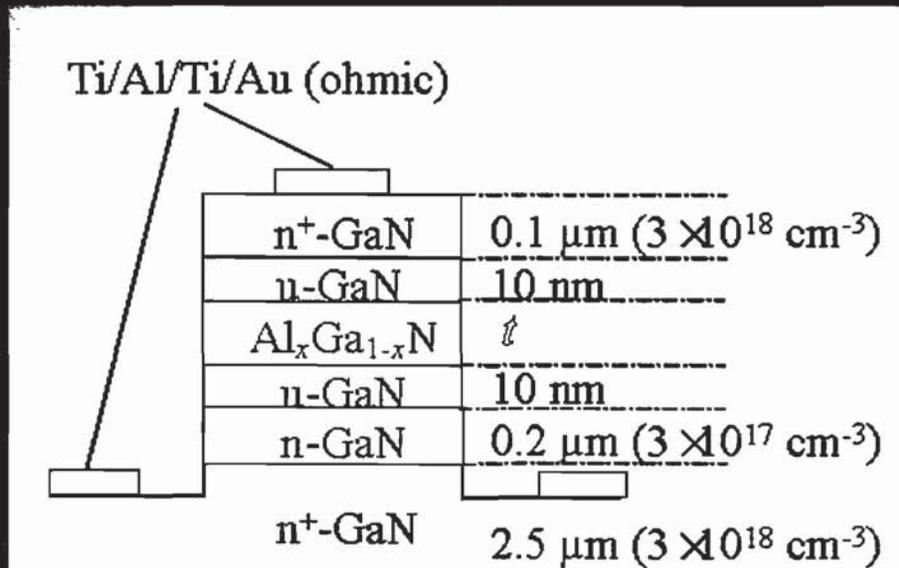
# Theoretical Modeling of Pressure Effect on n-I-n Sensor

Normalized change of current densities,  $(J_0 - J)/J_0$ , calculated for GaN/ $\text{Al}_x\text{Ga}_{1-x}\text{N}$ /GaN heterojunction under 10kbar hydrostatic pressure



- Current decreases with increasing pressure.
- Decrease of the current is more significant with higher x and the thicker AlGaIn layer.

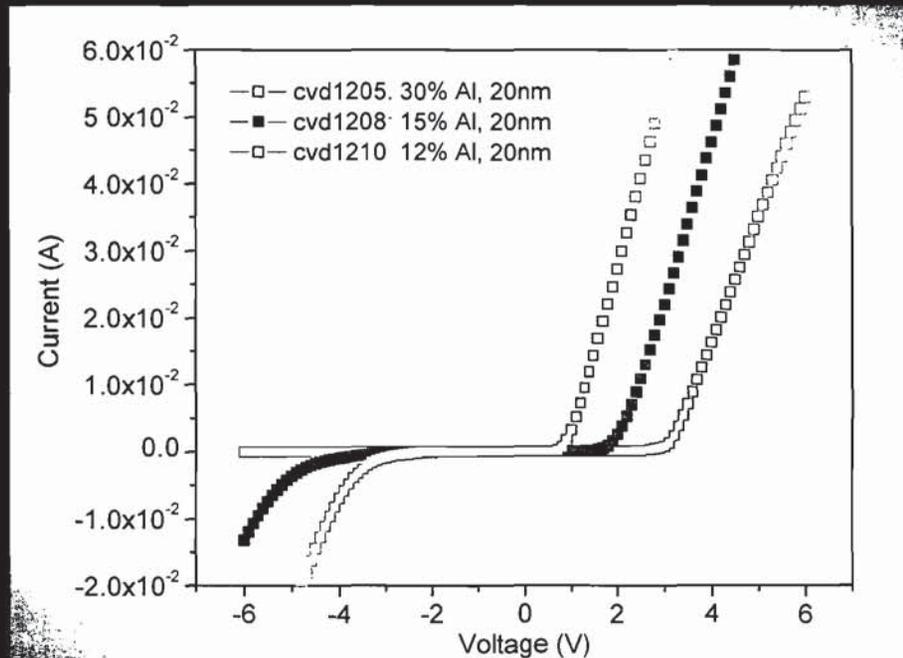
# GaN/Al<sub>x</sub>Ga<sub>1-x</sub>N/GaN (n-I-n) Sensor Structure



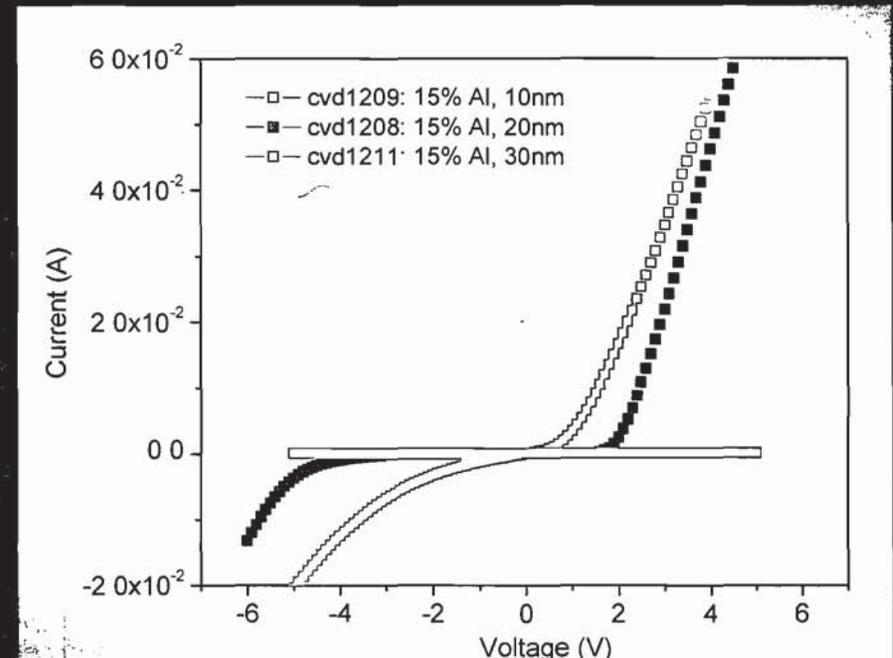
<i>t</i> (nm)	Al <sub>x</sub> Ga <sub>1-x</sub> N thickness: <i>t</i>		
	10nm	20nm	30nm
AIN %			
12%		CVD1210	
15%	CVD1209	CVD1208	CVD1211
30%		CVD1205	

# I-V Characteristics of n-I-n Sensors

Different Al compositions in  $\text{Al}_x\text{Ga}_{1-x}\text{N}$



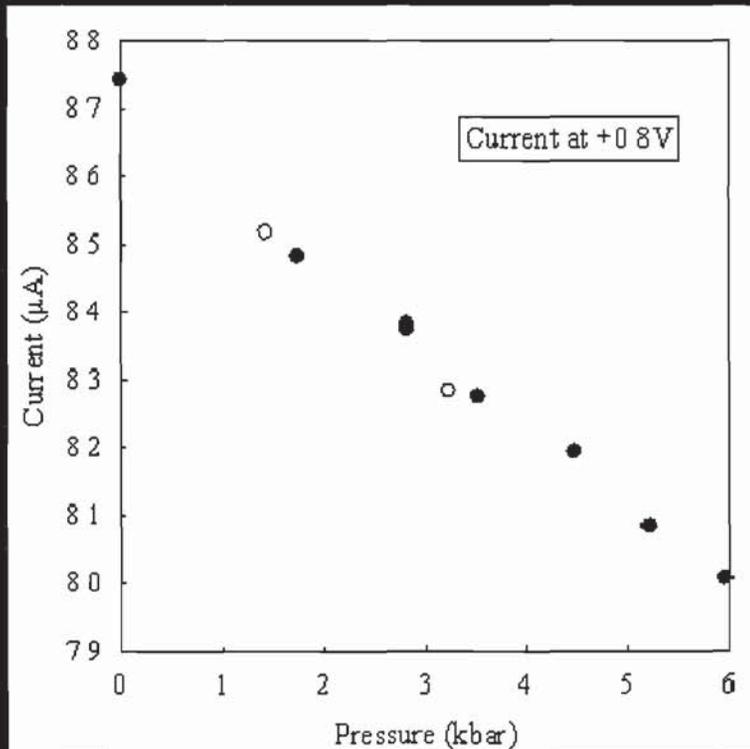
Different thicknesses of  $\text{Al}_x\text{Ga}_{1-x}\text{N}$



Higher turn-on voltage with higher Al content and thicker  $\text{Al}_x\text{Ga}_{1-x}\text{N}$

# Electrical Responses of n-I-n Sensor to Hydrostatic pressure

Pressure response measured for the n-GaN/Al<sub>0.15</sub>Ga<sub>0.85</sub>N /n-GaN

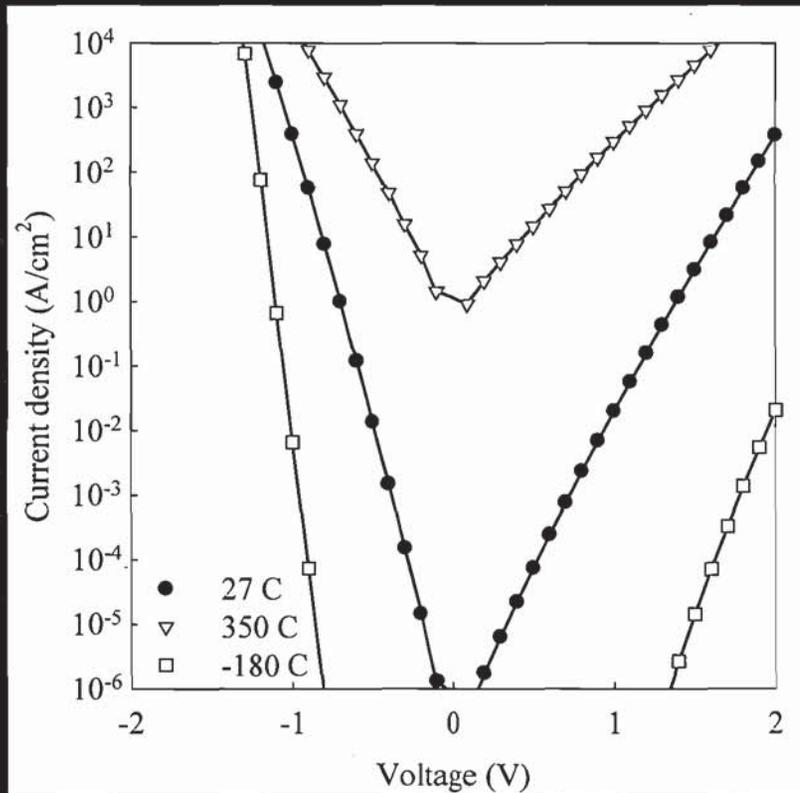


Current was measured under hydrostatic pressure at a fixed forward bias (+0.8 V) while the pressure was increased (solid dots) and decreased (open dots) as well.

- Linear decrease of current with increasing pressure
- Reversible response

# Theoretical Modeling of Temperature Responses of n-I-n Sensor

Current density vs. voltage plots for GaN/Al<sub>0.15</sub>Ga<sub>0.85</sub>N/GaN sensor at zero pressure

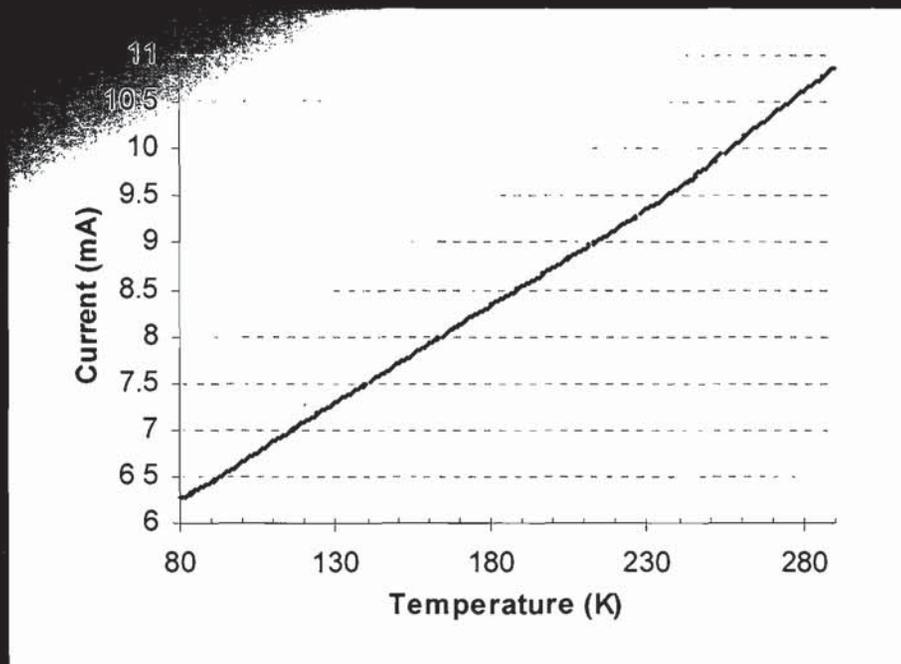


Calculated with doping density of  $3 \times 10^{18} \text{ cm}^{-3}$  for top GaN layer and  $3 \times 10^{17} \text{ cm}^{-3}$  for bottom GaN layer. 10 nm thick undoped AlGa<sub>0.15</sub>N layer is assumed.

Current decreases strongly with decreasing temperature.

# Temperature response of n-I-n sensor

Temperature response of GaN/Al<sub>0.15</sub>Ga<sub>0.85</sub>N/GaN sensor

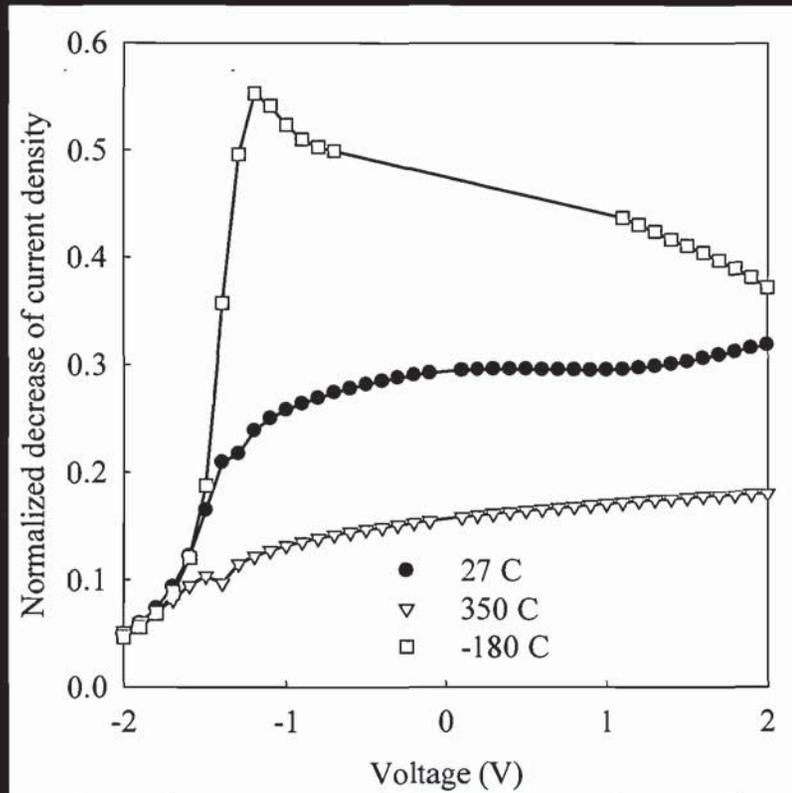


20 nm-thick Al<sub>0.15</sub>Ga<sub>0.85</sub>N layer  
The current was measured with  
a forward bias of 1.5 V.

- Good linearity between current and temperature

# Modeling of Temperature Responses of n-I-n under High Pressure

Normalized change of current density under 10kbar for GaN/Al<sub>0.15</sub>Ga<sub>0.85</sub>N/GaN



Calculated with doping density of  $3 \times 10^{18} \text{ cm}^{-3}$  for top GaN layer and  $3 \times 10^{17} \text{ cm}^{-3}$  for bottom GaN layer. 10 nm thick undoped AlGa<sub>0.15</sub>N layer is assumed.

- Current decreases with the applied pressure.
- The decrease gets more significant at lower temperatures.

# Pressure Responses of n-I-n Sensors

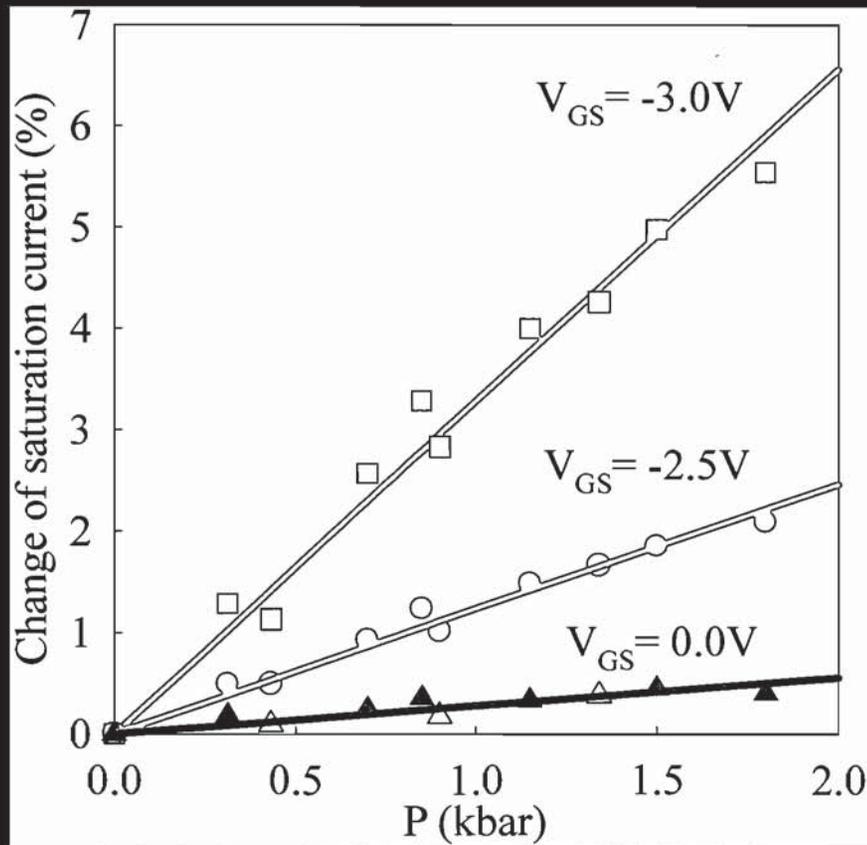
Sample Parameters		Maximum	Maximum
x	t <sub>AlGaN</sub> [nm]	PGF [GPa <sup>-1</sup> ]	SGF
0.12	20	-0.492	386
0.15	20	-0.541	425
0.30	20	-1.02	807
0.15	10	-0.626	492
0.15	30	-0.3	236

pressure gauge factor (PGF): normalized current change per unit pressure

Higher gauge factor measured for nIn sensors with higher Al content in Al<sub>x</sub>Ga<sub>1-x</sub>N

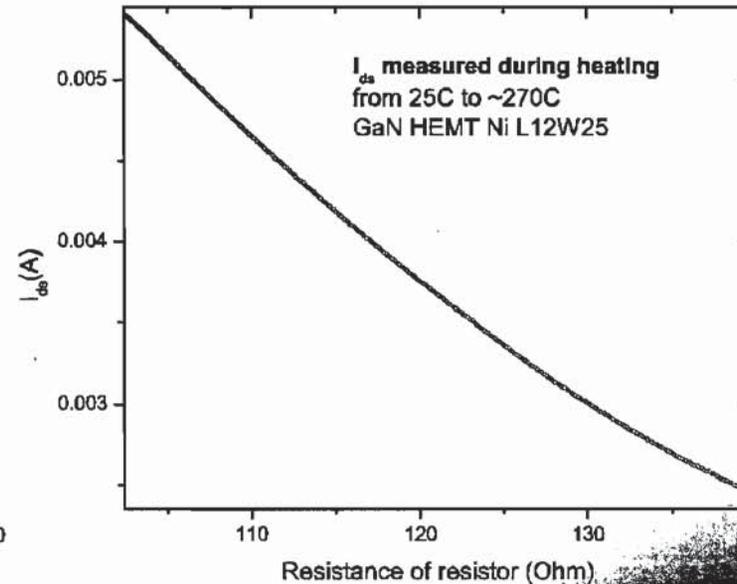
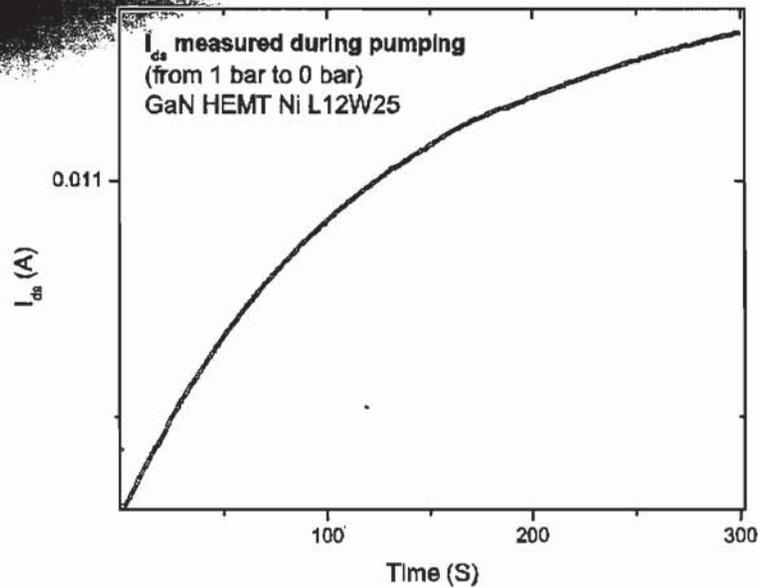
# Pressure Responses of $\text{Al}_{0.3}\text{Ga}_{0.7}\text{N}/\text{GaN}$ HEMT Sensor

Relative change of saturation current with pressure



- Linear decrease of current with increasing pressure
- Reversible response

# Pressure and Temperature Responses of $\text{Al}_{0.3}\text{Ga}_{0.7}\text{N}/\text{GaN}$ HEMT Sensor



# Summary

- Investigated n-GaN/ $\text{Al}_x\text{Ga}_{1-x}\text{N}$ /n-GaN (n-I-n) devices for pressure sensors in extreme environments.
- Theoretical modeling indicates decrease of electrical currents with increasing pressure due to the increase of polarization charge.
- The modeling predicts more significant decrease of current with higher AlN compositions in the  $\text{Al}_x\text{Ga}_{1-x}\text{N}$  layer and for the thicker  $\text{Al}_x\text{Ga}_{1-x}\text{N}$  layer.
- The vertical transport current measured with n-GaN/ $\text{Al}_x\text{Ga}_{1-x}\text{N}$ /n-GaN ( $X=0.12, 0.15$  &  $0.2$ ) sensors is consistent with the modeling studies.
- Linearity and reversibility in pressure response; n-GaN/ $\text{Al}_x\text{Ga}_{1-x}\text{N}$ /n-GaN is promising for high-pressure sensing in extreme environments.